

INFORMATION DISCLOSURE CITATION


Atty. Docket No.	03180.0327	Serial No.	10/615,228
Applicant	Kazuya FUKUHARA et al.		
Filing Date	July 9, 2003	Group:	1756

U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
CY	6,130,747	10/10/2000	Nomura et al.	356	239.2	

FOREIGN PATENT DOCUMENTS						
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
CY	Hiroshi Nomura, "Investigation of High-Precision Lithography Lens Aberration Measurement Based on Three-Beam Interference Theory: Sensitivity versus Coherent Factor and Variations with Dose and Focus, Optical Review, Vol. 7, No. 6 (July, 2000), p.p. 525-534

Examiner /Christopher Young/ (09/11/2006)	Date Considered 09/11/2006
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce



IDS Form PTO/SB/08: Substitute for form 1449A/PTC				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Application Number: 10/615,228	
(Use as many sheets as necessary)				Filing Date: July 9, 2003	
				First Named Inventor: Kazuya Fukuhara	
				Art Unit: 1756	
				Examiner Name: C. Young	
Sheet	1	of	1	Attorney Docket Number: 3180.0327	

U.S. PATENTS AND PUBLISHED U.S. PATENT APPLICATIONS					
Examiner Initials	Cite No. ¹	Document Number	Issue or Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
CY		US-2002/0086224 A1	7/4/02	Kanda	
CY		US-5,933,219	8/3/99	Unno	
CY		US-5,541,026	7/30/96	Matsumoto	
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Note: Submission of copies of U.S. Patents and published U.S. Patent Applications is not required.

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation ⁶
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				
CY		JP 6-181167	6/28/94	Canon Inc.		Abstract

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Translation ⁶
CY		Search Report issued by Netherlands Patent Office for Netherlands Application No. 135218, dated July 26, 2005	

Examiner Signature	/Christopher Young/ (09/11/2006)	Date Considered	09/11/2006
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